	Document ID	Issue Date	Pages	Title	Current OR
1	US 20040142251 A1	20040722	22	Method and apparatus for performing model-based layout conversion for use with dipole illumination	430/5
2	US 20040132250 A1	20040708	75	Preventing dielectric thickening over a gate area of a transistor	438/264
3	US 20040067423 A1	20040408	24	Hybrid phase-shift mask	430/5
4	US 20040063000 A1	20040401	20	Chromeless phase mask layout generation	430/5
5	US 20040033426 A1	20040219	29	Lithographic apparatus, device manufacturing method, and device manufactured thereby	430/22
6	US 20040010770 A1	20040115	16	Method and apparatus for decomposing semiconductor device patterns into phase and chrome regions for chromeless phase lithography	716/21
7	US 20040006757 A1	20040108	17	Method and apparatus for defining mask patterns utilizing a spatial frequency doubling technique	716/19
8	US 20040003368 A1	20040101	21	Method and apparatus for performing rule-based gate shrink utilizing dipole illumination	716/19
9	US 20030230967 A1	20031218	43	Visible image receiving material, conductive pattern material and organic electroluminescence element, using member having surface hydrophilicity	313/483

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10	US 20030223080 A1	20031204	24	Retroreflector coating for an interferometer	356/500
11	US 20030223050 A1	20031204	24	Method for photolithography using multiple illuminations and a single fine feature mask	355/51
12	US 20030160980 A1	20030828	97	Graphics engine for high precision lithography	358/1.9
13	US 20030107465 A1	20030612	54	Passive element component and substrate with built-in passive element	338/13
14	US 20030082981 A1	20030501	95	Manufacturing methods for electron source and image forming apparatus	445/6
15	US 20030073013 A1	20030417	23	Method for improved lithographic patterning utilizing multiple coherency optimized exposures and high transmission attenuated PSM	430/30
16	US 20030071331 A1	20030417	39	Semiconductor device and structure for mounting the same	257/669
17	US 20030049881 A1	20030313	20	Article to be processed having ID, and production method thereof	438/62
18	US 20030026471 A1	20030206	36	Overlay marks, methods of overlay mark design and methods of overlay measurements	382/144
19	US 20030021467 A1	20030130	36	Overlay marks, methods of overlay mark design and methods of overlay measurements	382/151
20	US 20030021466 A1	20030130	37	Overlay marks, methods of overlay mark design and methods of overlay measurements	382/151
21	US 20030021465 A1	20030130	37	Overlay marks, methods of overlay mark design and methods of overlay measurements	382/151

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22	US 20020180027 A1	20021205	50	Semiconductor module and method of making the device	257/700
23	US 20020180015 A1	20021205	51	Semiconductor module	257/678
24	US 20020171089 A1	20021121	52	Display unit and semiconductor light emitting device	257/88
25	US 20020166107 A1	20021107	36	Method and apparatus for generating masks utilized in conjunction with dipole illumination techniques	716/19
26	US 20020145588 A1	20021010	28	Optically based machine input control device	345/156
27	US 20020135720 A1	20020926	140	Liquid crystal display device and method for fabricating the same	349/122
28	US 20020063332 A1	20020530	37	Semiconductor device and method for manufacturing the same and semiconductor device-mounted structure	257/738
29	US 20020019305 A1	20020214	70	Gray scale all-glass photomasks	501/56
30	US 20020015899 A1	20020207	24	Hybrid phase-shift mask	430/5
31	US 20020013055 A1	20020131	63	Method of manufacturing semiconductor device	438/689
32	US 20020008799 A1	20020124	121	Liquid crystal display unit	349/43

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33	US 20020006558 A1	20020117	85	Structure for pattern formation, method for pattern formation, and application thereof	430/7
34	US 20020004172 A1	20020110	14	Optical recording film and process for production thereof	430/1
35	US 20010041407 A1	20011115	15	Trench-gate semiconductor devices	438/270
36	US 20010026331 A1	20011004	95	Liquid crystal display device	349/43
37	US 20010005031 A1	20010628	59	Power semiconductor device	257/401
38	US 6791178 B2	20040914	49	Multi-chip module including semiconductor devices and a wiring substrate for mounting the semiconductor devices	257/699
39	US 6774043 B2	20040810	61	Method of manufacturing semiconductor device	438/705

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40	US 6753253 B1	20040622	326	Method of making wiring and logic corrections on a semiconductor device by use of focused ion beams	438/676
41	US 6707523 B2	20040316	91	Liquid crystal display device wherein pixels having particular metal layer between alignment film and protective film	349/141
42	US 6630381 B1	20031007	72	Preventing dielectric thickening over a floating gate area of a transistor	438/260
43	US 6623895 B2	20030923	23	Hybrid phase-shift mask	430/5
44	US 6610934 B2	20030826	49	Semiconductor module and method of making the device	174/264
45	US 6586800 B2	20030701	14	Trench-gate semiconductor devices	257/330
46	US 6563557 B2	20030513	128	Liquid crystal display device including a stack of plurality of resin film and method for fabricating the same	349/74
47	US 6553562 B2	20030422	35	Method and apparatus for generating masks utilized in conjunction with dipole illumination techniques	716/19

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48	US 6548263 B1	20030415	79	Miniaturized cell array methods and apparatus for cell-based screening	435/7.2
49	US 6524771 B2	20030225	13	Optical recording film and process for production thereof	430/290
50	US 6524756 B1	20030225	67	Gray scale all-glass photomasks	430/5

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51	US 6498368 B2	20021224	56	Power semiconductor device	257/341
52	US 6489720 B1	20021203	52	Image-forming apparatus and fabrication method therefor	313/558
53	US 6479193 B1	20021112	12	Optical recording film and process for production thereof	430/1
54	US 6378199 B1	20020430	68	Multi-layer printed-wiring board process for producing	29/830
55	US 6337175 B1	20020108	19	Method for forming resist pattern	430/322
56	US 6312864 B1	20011106	15	Methods for production of patterned calcined inorganic film	430/198
57	US 6304309 B1	20011016	129	Liquid crystal display device and method of manufacturing the same	349/156
58	US 6294313 B1	20010925	79	Pattern forming body, pattern forming method, and their applications	430/302
59	US 6233044 B1	20010515	45	Methods and apparatus for integrating optical and interferometric lithography to produce complex patterns	355/67
60	US 6170394 B1	20010109	38	Method of preparing and using a plastic mask for paste printing	101/129

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61	US 6136652 A	20001024	74	Preventing dielectric thickening over a channel area of a split-gate transistor	438/260
62	US 6120975 A	20000919	16	Methods for production of a plasma display panel	430/321
63	US 6093503 A	20000725	65	Non-aqueous electrolyte lithium secondary cell	429/61
64	US 6063476 A	20000516	40	Method of fabricating plastic mask for paste printing, plastic mask for paste printing, and paste printing method	428/131
65	US 5963812 A	19991005	57	Manufacturing method of a semiconductor apparatus having an electron donative surface in a side wall portion	438/304
66	US 5887520 A	19990330	36	Method of fabricating plastic mask for paste printing with an excimer laser	101/128.4
67	US 5739898 A	19980414	94	Exposure method and apparatus	355/53
68	US 5731086 A	19980324	32	Debossable films	428/411.1

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69	US 5677867 A	19971014	70	Memory with isolatable expandable bit lines	365/185.01
70	US 5622634 A	19970422	48	Method of manufacturing electron-emitting device, electron source and image-forming apparatus	216/40
71	US 5580808 A	19961203	63	Method of manufacturing a ROM device having contact holes treated with hydrogen atoms and energy beam	438/128
72	US 5569614 A	19961029	66	Method of forming metal pattern including a schottky diode	438/571
73	US 5527730 A	19960618	63	Method of forming a capacitor having contact hole treated with hydrogen atoms and energy beam	438/256
74	US 5508803 A	19960416	20	Method and apparatus for monitoring lithographic exposure	356/243.5
75	US 5494762 A	19960227	65	Non-aqueous electrolyte lithium secondary cell	429/221

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76	US 5328810 A	19940712	30	Method for reducing, by a factor or 2.sup.-N, the minimum masking pitch of a photolithographic process	430/313
77	US 5262341 A	19931116	36	Blanking aperture array and charged particle beam exposure method	438/618
78	US 5248990 A	19930928	16	Process for producing optical recording medium for optical data recording and reproduction	347/262
79	US 5144142 A	19920901	37	Blanking aperture array, method for producing blanking aperture array, charged particle beam exposure apparatus and charged particle beam exposure method	250/396R
80	US 4273812 A	19810616	14	Method of producing material patterns by evaporating material through a perforated mask having a reinforcing bridge	427/96.8